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*Coherent and incoherent dynamics of electronic
surface states of Si(111) and Si(001)*

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Coherent and incoherent dynamics of electronic surface states of Si(111) and Si(001)

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1. Motivation
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 3. Excitation Mechanism (2PPE, SHG)
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 5. Conclusion
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Motivation

Why Study Surface Carrier Dynamics?

- Model for dynamics at interfaces
- Surface photochemistry
 - relaxation rate of photoexcited carriers
 - yield of photochemical reactions
- Performance of devices
 - accurate fundamental carrier relaxation rates
 - correct modeling of state-of-the-art Si devices

Why Probe Relaxation Times with Nonlinear Optical Techniques?

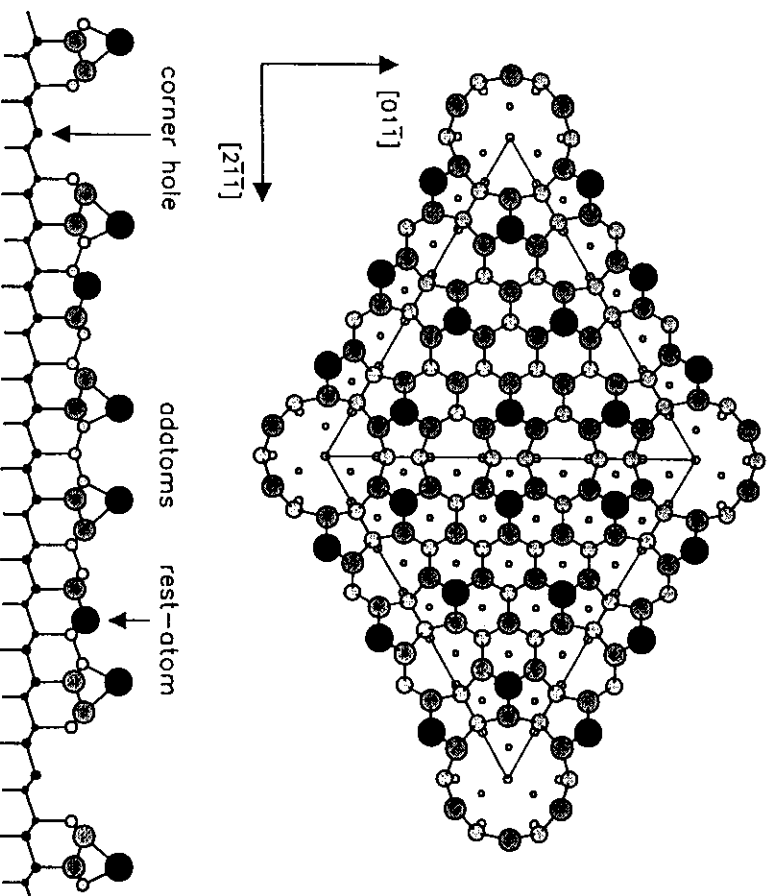
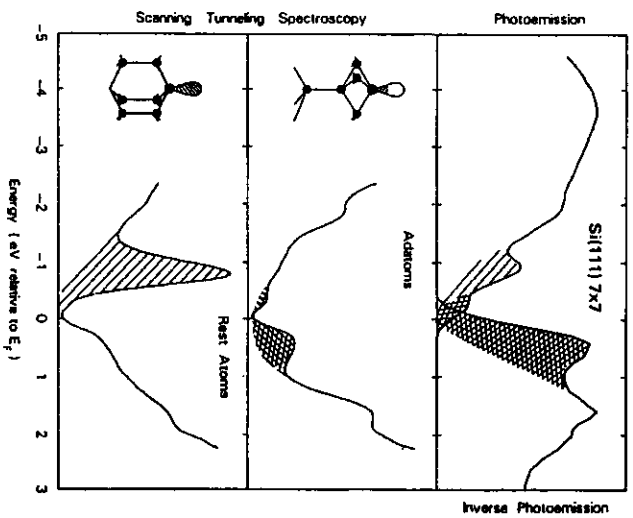
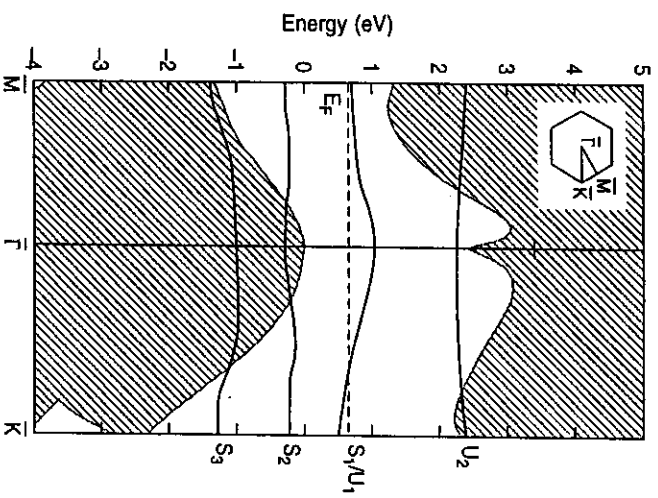
- Genuine surface signal for $\chi^{(2)}$, $\chi^{(4)}$
- Applicable at high excitation conditions
- Applicable to many different interfaces

This work:

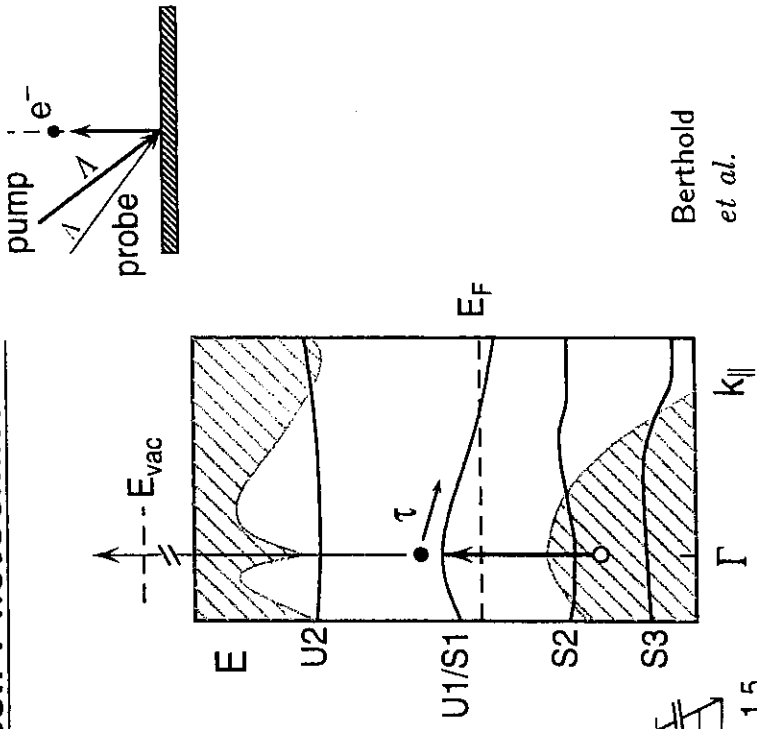
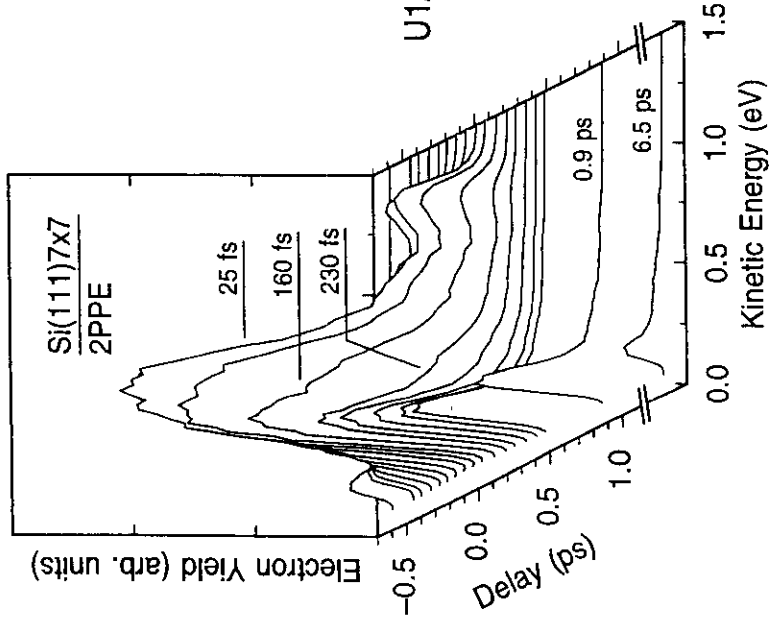
- Combination of SHG and DFWM
 - coherent technique to study carrier scattering processes at surfaces
- Opportunity of learning about some of the most fundamental quantum mechanical processes in surfaces

Si(111)7x7

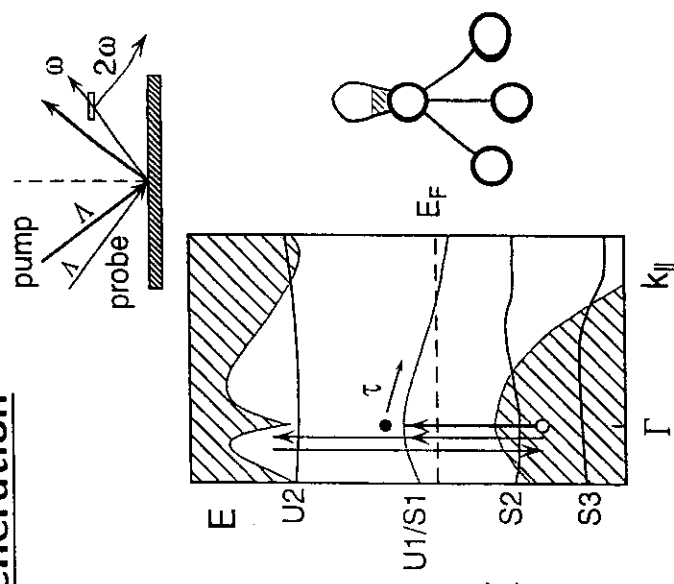
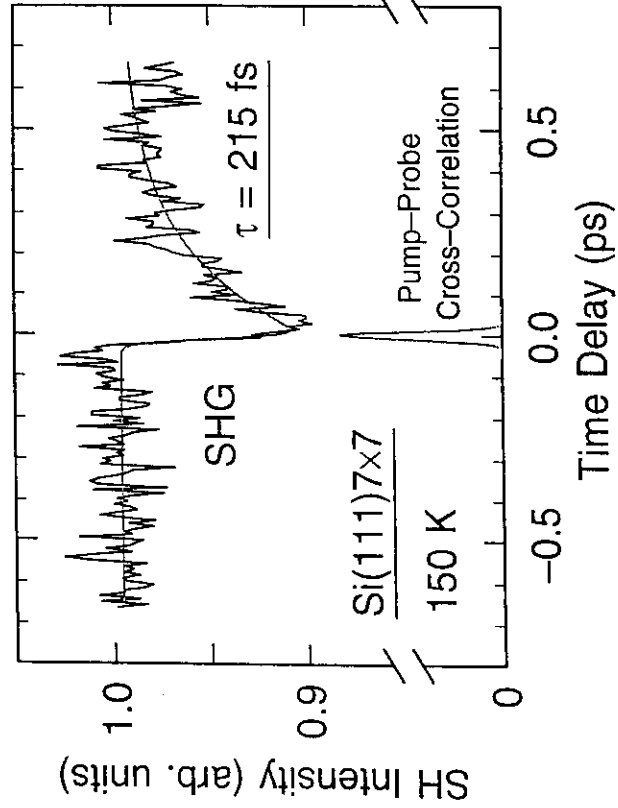
F.J. Himpsel



Time-Resolved Two-Photon Photoemission



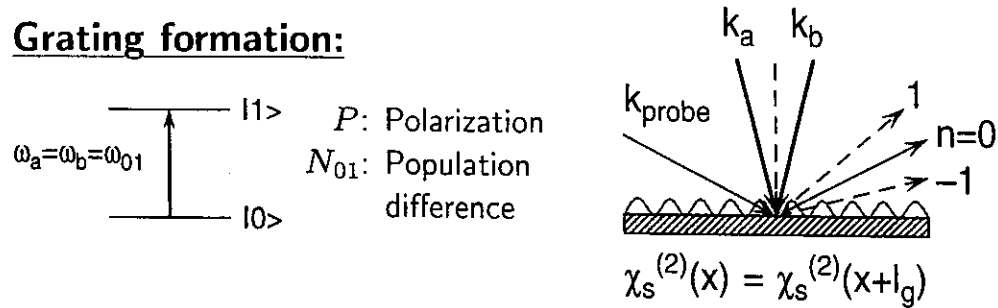
Pump-Probe Second-Harmonic Generation



phys. stat. sol. (a) 175, 169 (1999).

Diffraction from Transient Gratings

Grating formation:



$$\frac{\partial}{\partial t} P_j^{(1)} = \frac{i\mu}{\hbar} E_j - \frac{1}{T_2} P_j^{(1)}, \quad j = a, b$$

$$\frac{\partial}{\partial t} N_{01}^{(2)} = \frac{i\mu}{\hbar} (E_a P_b^{*(1)} - P_a^{(1)} E_b^*) + \text{c.c.} - \frac{1}{T_1} N_{01}^{(2)}$$

$$\frac{\partial}{\partial t} P_d^{(3)} = -2 \frac{i\mu}{\hbar} E_p N_{01}^{(2)} - \frac{1}{T_2} P_d^{(3)}$$

Information from diffracted signal (limiting cases):

a) delay $\tau_b = 0, \tau_{\text{probe}} > 0$
 $\Rightarrow$ Population relaxation T_1 (& diffusivity)

b) delay $\tau_b > 0, \tau_{\text{probe}} = \tau_b$
 $\Rightarrow$ Dephasing T_2

self-diffraction: $k_{\text{probe}} \equiv k_b$

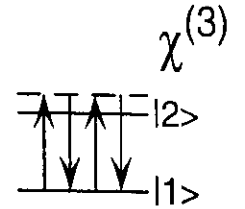
DFWM vs. SH-Diffraction

Four-wave mixing

- bulk (& surface) sensitive

$$P^{(3)}(K_d^{(\pm 1)}; \omega) = \chi^{(3)} : E_a^*(k_a) E_b^2(k_b)$$

$$K_{d,x}^{(\pm 1)} = k_{b,x} \pm (k_{b,x} - k_{a,x})$$

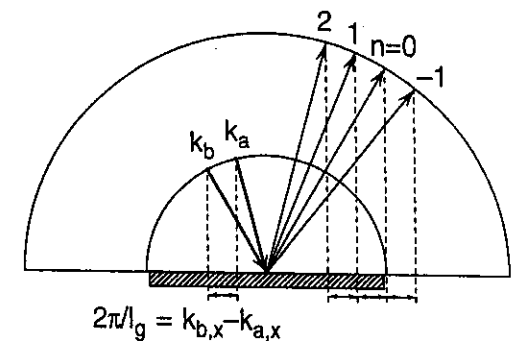
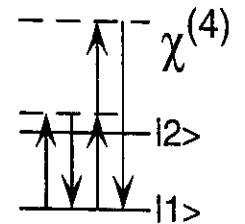


2ω diffraction (five-wave mixing)

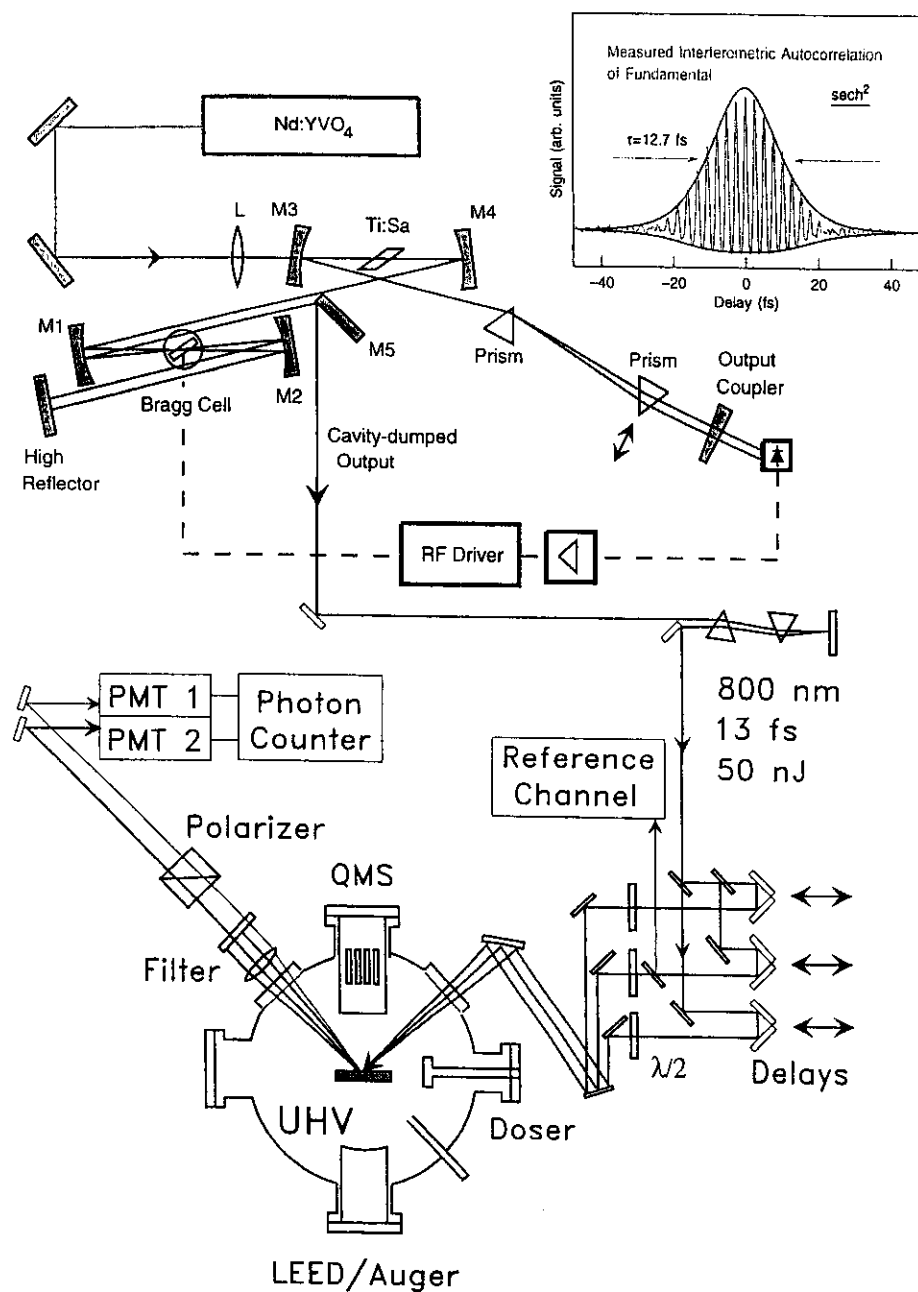
- surface sensitive

$$P^{(4)}(K_d^{(\pm 1)}; 2\omega) = \chi^{(4)} : E_a^*(k_a) E_b^3(k_b)$$

$$K_{d,x}^{(\pm 1)} = 2k_{b,x} \pm (k_{b,x} - k_{a,x})$$



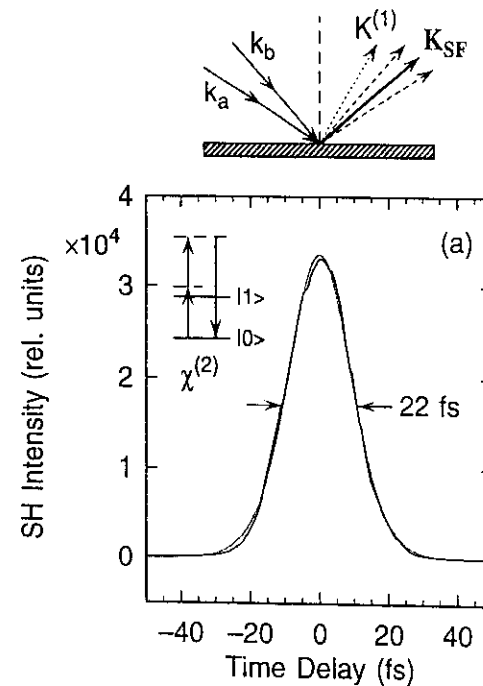
Experimental Setup



Experimental Data

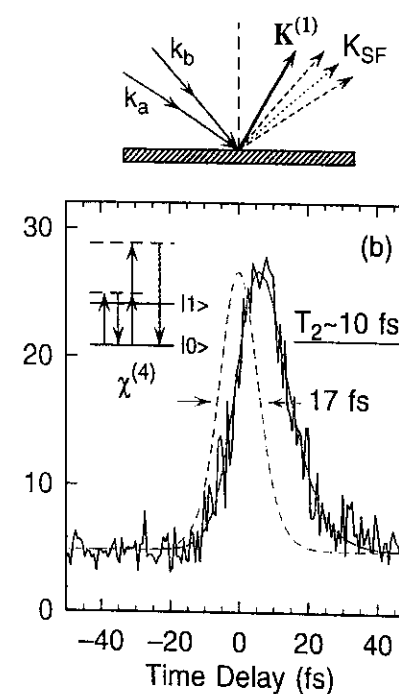
Si(111)7×7, 80 K

Sum-Frequency Signal



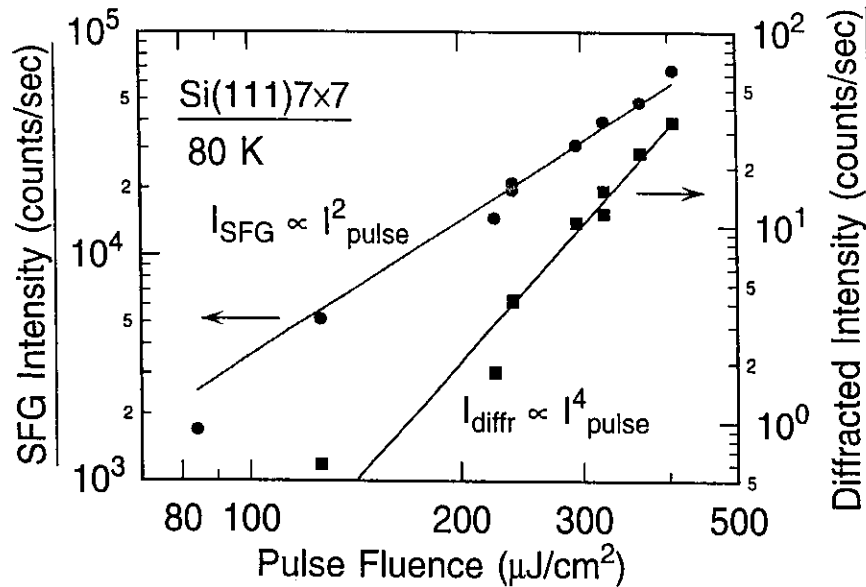
⇒ Pulse duration:
 $\tau_p < 14$ fs
(on sample in UHV)

Diffracted Signal



⇒ Dephasing time:
 $T_2 \simeq 10$ fs

Pulse Fluence Dependence



Sum-frequency signal

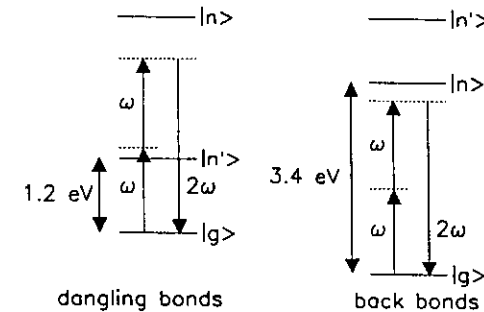
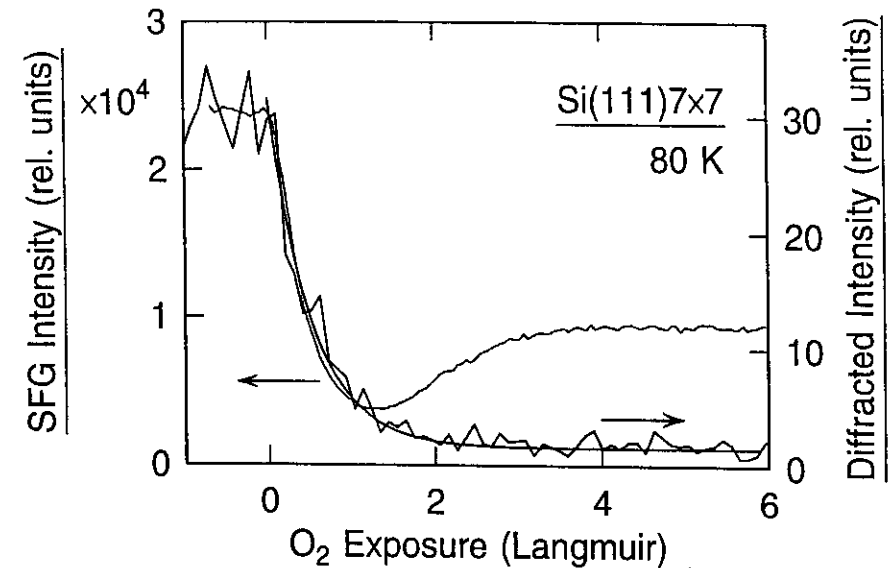
$$P_s^{(2)}(K_{\text{SF}}; 2\omega) = \chi_s^{(2)} : E_a(k_a)E_b(k_b)$$

Self-diffracted signal

$$P_s^{(4)}(K_d^{(+1)}; 2\omega) = \chi_s^{(4)} : E_a^*(k_a)E_b^3(k_b)$$

$$I_d(2\omega) \propto |P_s^{(4)}(2\omega)|^2$$

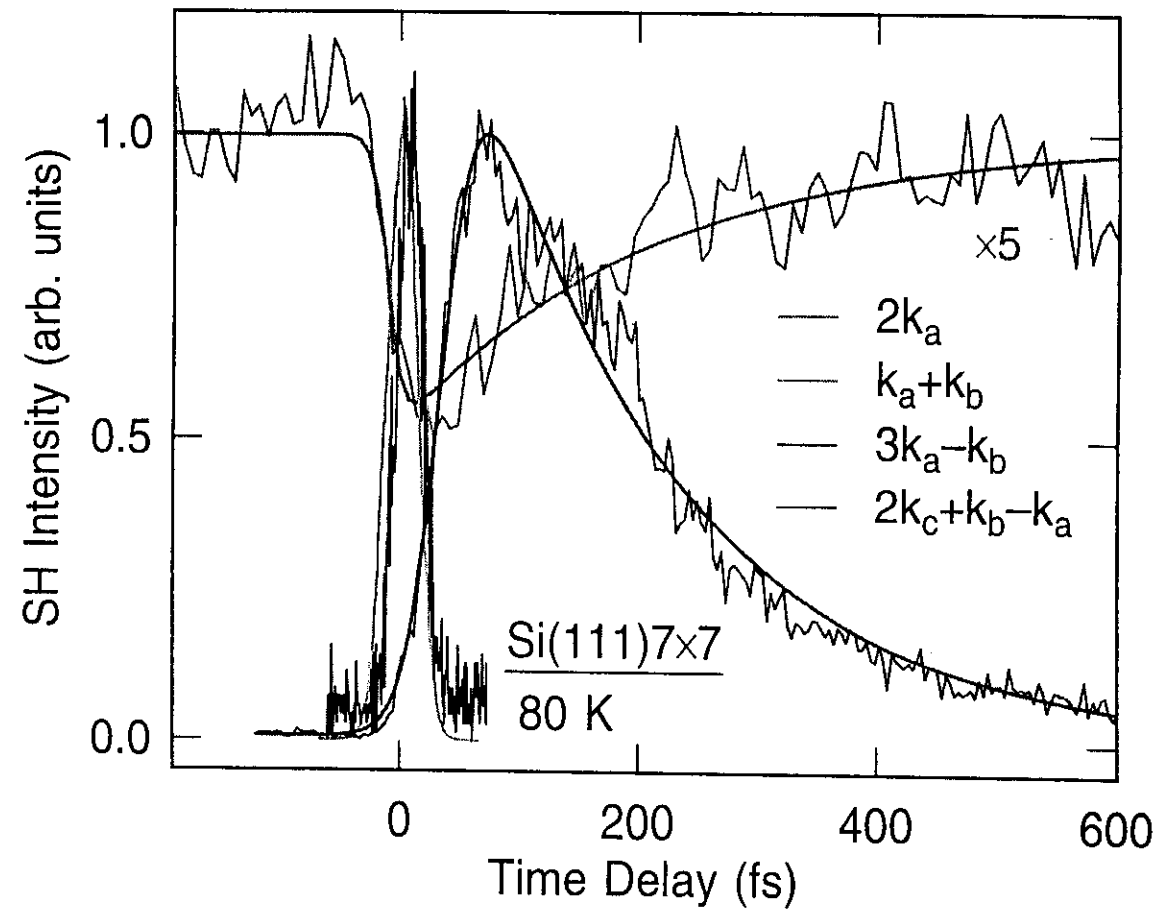
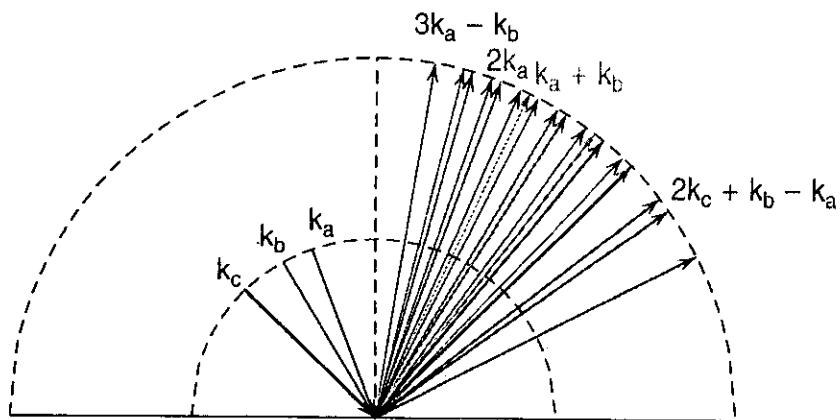
Coverage Dependence



Appl. Phys. B 68,
383 (1999).

- minimum in the SFG signal due to destructive interference between dangling bond and back bond terms in $\chi_s^{(2)}$
- no minimum in diffracted SHG signal: the only contribution is dangling bond term $\chi_{\text{db}}^{(4)}$

SH Signals into Various Directions



Numerical Simulation

- density-matrix formalism:
semi-classical approach
 - electromagnetic light field treated classically
 - material system treated quantum-mechanically
by its density matrix ρ
 - light-matter interaction Hamiltonian
in the electric-dipole approximation
- Liouville equation
$$\frac{d}{dt}\rho = \frac{1}{i\hbar}[H, \rho] + \frac{d}{dt}\rho_{\text{relax}}$$
- numerical integration of Bloch equations
for $\chi^{(4)}$ second-harmonic diffraction
- for independent three-level system with detuning
- to 4th order in terms of the electric field E
- relaxation-time (Markovian) approximation
- summation over range of both detunings
to simulate inhomogeneous broadening
- slowly-varying-envelope approximation
for sech^2 or Gaussian pulses

Conclusion

- Demonstration of surface sensitive transient
grating experiment ($\chi_s^{(4)}$ process)
 - 2-beam self-diffraction geometry
 - 3-beam diffraction geometry
- Excellent time resolution due to cavity-dumped
Ti:sapphire laser (pulse duration in UHV chamber
< 14 fs)

Pump-Probe

Relaxation Times

- T_1 time:
population relaxation
- origin:
multiple scattering
of excited electrons
out of optically coupled
region in k -space
- $T_1 = 100 \text{ fs} - 2 \text{ ps}$

Dephasing Times

- T_2 time:
polarization relaxation
- origin:
single, phase-destroying
scattering processes
→ eventual loss
of coherence
- $T_2 \simeq 10 \text{ fs}$
(inhom. broadening)